

**REMARKS**

Please reconsider this application in view of the above amendments and the following remarks.

- Claims 1-30 are pending.
- Claims 17-30 are withdrawn
- Claims 1-16 are rejected.
- Claims 1, 12, and 17 are currently amended.

Claims 1, 12, and 17 have been amended to remove the recitation that the carbon deposit is implanted “by plasma reaction.”

Additionally, Claims 1, 12, and 17 have been amended to recite that carbon be “implanted on a molecular level.” Applicant uses the phrase “on a molecular level” to indicate that the compounds being implanted or the compounds after implantation are atomic or molecular sized rather than bulk materials. Support for this amendment can be found throughout the specification as a whole. Specifically, the specification paragraph [008] discloses the implantation of carbon using plasma. One of ordinary skill in the art would recognize that the implantation of carbon with a plasma would inherently involve the implantation of carbon ions, which are atomic sized.

**Art-Based Rejections**

The cited references of record do not teach implantation “on a molecular level” as Applicant uses that term.

Please remove the outstanding art rejections.

Claims 17-30 are in essence process claims for making the products of claims 1-16 and are commensurate in scope with those claims. Therefore, since Claims 1-16 are allowable, please rejoin and examine process Claims 17-30.

Since all claims are in a condition for allowance, please issue a Notice of Allowability so stating. If I can be of any help, please contact me.

Respectfully submitted,

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